L Number	Hits	Search Text	DB	Time stamp
- Nambel	10	LISENKER-B LISENKER-BORIS-S LISENKER-B-S	USPAT;	2004/09/16 09:49
-	10	FIDERIVEY-D FIDERIVEY-DOINTO O FIDERIVEY-D-O	US-PGPUB;	200 1/03/10 03.43
			EPO; JPO;	
			DERWENT	
	3	JANKELEVICH	USPAT;	2004/09/02 08:30
-]	JANNELEVICII	US-PGPUB;	200 1/05/02 00.50
			EPO; JPO;	
			DERWENT	
_	32	KIZILYALLI and deuter\$8	USPAT;	2004/09/16 09:52
	J2		US-PGPUB;	200 1/05/10 05.52
			EPO; JPO;	
			DERWENT	
_	3684	438/301.ccls. 438/303.ccls. 438/595.ccls. 438/786.ccls.	USPAT;	2004/09/16 09:50
	3001	438/791.ccls. 427/255.29.ccls. 427/255.39.ccls.	US-PGPUB	200 1/05/10 05:50
		427/255.393.ccls. 427/255.394.ccls.	33 . 3. 35	
_	1569	deuter\$8 and (cvd (chemical adj vapor) tetrachlorosilane tcs	USPAT;	2004/09/16 10:00
	1509	"sicl.sub.4" hexadichlorosilane hcd "si.sub.2 cl.sub.6"	US-PGPUB	
		"si.sub.2cl.sub.6")	00 / 0.00	
_	12	(438/301.ccls. 438/303.ccls. 438/595.ccls. 438/786.ccls.	USPAT;	2004/09/16 10:06
		438/791.ccls. 427/255.29.ccls. 427/255.39.ccls.	US-PGPUB	,,
		427/255.393.ccls. 427/255.394.ccls.) and deuter\$8		
_	11	deuter\$8 and (tetrachlorosilane tcs "sicl.sub.4"	EPO; JPO;	2004/09/16 11:06
		hexachlorodisilane hcd "si.sub.2 cl.sub.6" "si.sub.2cl.sub.6")	DERWENT;	. ,
		,	IBM_TDB	
-	143	deuter\$8 and (cvd (chemical adj vapor)) and (tetrachlorosilane	USPAT;	2004/09/16 11:14
		tcs "sicl.sub.4" hexachlorodisilane hcd "si.sub.2 cl.sub.6"	US-PGPUB	
-		"si.sub.2cl.sub.6")		
-	28	deuter\$8 and ((silicon adj (oxynitride nitride)) sion sio?n? si?n?	EPO; JPO;	2004/09/17 08:00
		"si.sub.3 n.sub.4" "si.sub.3n.sub.4")	DERWENT;	
			IBM_TDB	
-	51	deuter\$8 same (cvd (chemical adj vapor)) same ((silicon adj	USPAT;	2004/09/16 14:02
		(oxynitride nitride)) sion sio?n? si?n? "si.sub.3 n.sub.4"	US-PGPUB	
		"si.sub.3n.sub.4")		G
-	8	deuter\$8 and ((silicon adj oxynitride) sino sion sio?n?	EPO; JPO;	2004/09/17 08:24
1		"sio.sub.xn.sub.y" "sio.sub.x n.sub.y" "sin.sub.xo.sub.y"	DERWENT;	
		"sin.sub.x o.sub.y" "si.sub.xo.sub.yn.sub.z" "si.sub.x o.sub.y	IBM_TDB	
1		n.sub.z" "si.sub.xn.sub.yo.sub.z" "si.sub.x n.sub.y o.sub.z")		
-	29	deuter\$8 same ((silicon adj oxynitride) sino sion sio?n?	USPAT;	2004/09/17 08:24
		"sio.sub.xn.sub.y" "sio.sub.x n.sub.y" "sin.sub.xo.sub.y"	US-PGPUB	
		"sin.sub.x o.sub.y" "si.sub.xo.sub.yn.sub.z" "si.sub.x o.sub.y		
		n.sub.z" "si.sub.xn.sub.yo.sub.z" "si.sub.x n.sub.y o.sub.z")		2004/00/17 10 57
-	137	(spacer near nitride) same (etch\$6 with (gas dry vertical\$4	USPAT;	2004/09/17 10:37
		anisotropic\$8)) same ((source drain) with implant\$8)	US-PGPUB	2004/00/47 40 27
-	49	((spacer near nitride) same (etch\$6 with (gas dry vertical\$4	USPAT;	2004/09/17 10:37
	İ	anisotropic\$8)) same ((source drain) with implant\$8)) and	US-PGPUB	
1		dram		